

<b>INFORMATION DISCLOSURE CITATION</b> (Use several sheets if necessary)	<b>Attorney Docket No.:</b> 46884-5429 <b>Applicants:</b> Seiichi NAGATA	<b>Serial No.:</b> 10/551,195 <b>Page</b> 1 of 1
<b>PTO Form 1449</b>	<b>Filing Date:</b> September 29, 2005	<b>Group Art Unit:</b> Unassigned

### U.S. PATENT DOCUMENTS

*Examiner Initial	Document Number	Date	Name	Class	Sub Class	Filing Date

### FOREIGN PATENT DOCUMENTS

	Document Number	Date	Country	Class	Sub Class	<u>Translation</u>	
						YES	NO
/JL/	10-133047	May 22, 1998	JP			Abstract	
/JL/	11-242125	Sept. 7, 1999	JP			Abstract	
/JL/	2000-047045	Feb. 18, 2000	JP			Abstract	
/JL/	11-014848	Jan. 22, 1999	JP			Abstract	
/JL/	10-160950	Jun. 19, 1998	JP			Abstract	
/JL/	10-133048	May 22, 1998	JP			Abstract	
/JL/	10-300963	Nov. 13, 1998	JP			Abstract	
/JL/	61-180449	Aug. 13, 1986	JP			Abstract	
/JL/	52-063685	May 26, 1977	JP			Abstract	
/JL/	09-292540	Nov. 11, 1997	JP			Abstract	

### OTHER DOCUMENTS

(Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.) date, page(s), volume-issue number(s), publisher, city and/or country where published.)

/JL/	M.E. Lines, "Can The Minimum Attenuation of Fused Silica Be Significantly Reduced By Small Compositional Variations? I. Alkali Metal Dopants"; Journal of Non-Crystalline Solids 171, 1994, pp. 209-218
/JL/	M.E. Lines, "Can The Minimum Attenuation Of Fused Silica Be Significantly Reduced By Small Compositional Variations? II. Combined Fluorine and Alkali Metal Dopants", Journal of Non-Crystalline Solids 171, 1994, pp. 219-227
/JL/	K. SAITO et al., "A New Method of Developing Ultralow-Loss Glasses", J. Appl. Phys. 81 (11), June 1, 1997, pp. 7129-7134
/JL/	Fumiaki HANAWA et al., "Fabrication of Pure Silica Core Fibers By VAD Method", Transactions of the Institute of Electronics and Communication Engineers of Japan, Part C, Vol. J68C, No. 8, Aug. 1985, pp. 597-604, including English language abstract
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/JL/	P.K. BACHMANN et al., "Thermal Expansion Coefficients of Doped And Undoped Silica Prepared By Means Of PCVD", Journal of Materials Science 23, 1988, pp. 2584-2588
/JL/	K. KOBAYASHI, "Structural Interpretation Of The Low Temperature Reflow Of Borophosphosilicate Glasses Doped With BF <sub>2</sub> By Ion Implantation", Glass Technology, Vol. 29, No. 6, December 1988, pp. 253-257
/JL/	Hiroshi TANAKA et al., "Sintering Temperature of Porous Glass And Transition Temperature Of High Silica Glass", Yogyo-Kyokai-Shi, Vol. 94, No. 6, 1986, pp. 564-570, including English language abstract
/JL/	Morio TAKAHASHI et al., "Fabrication and Characteristics Of Three-Dimensionally Buried Porous Silicon Optical Waveguides", Journal of Applied Physics, Vol. 86, No. 9, November 1, 1999, pp. 5274-5278
/JL/	Gabriella MAIELLO et al., "Light Guiding In Oxidised Porous Silicon Optical Waveguides", Thin Solid Films 297, 1997, pp. 311-313
/JL/	V.P. BONDARENKO et al., "Optical Waveguide Based On Oxidized Porous Silicon", Microelectronic Engineering 28, 1995, pp. 447-450

Examiner	/Jonathan Langman/	Date Considered 12/30/2008
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